

Docket No.: 50090-334

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of
Masanobu IWASAKI, et al.

Serial No.: 09/934,474

Filed: August 23, 2001

For: POLISHING SOLUTION SUPPLY SYSTEM, METHOD OF SUPPLYING
POLISHING SOLUTION, APPARATUS FOR AND METHOD OF POLISHING
SEMICONDUCTOR SUBSTRATE AND METHOD OF MANUFACTURING
SEMICONDUCTOR DEVICE

71861
PATENT
ENTERED

AM D7-2 RECEIVED
JUL 23 2002
TECHNOLOGY CENTER R3700

Commissioner for Patents
Washington, DC 20231

Sir:

The following Amendment and Remarks are submitted in response to the Office Action dated April 18, 2002, pursuant to the provisions of 37 C.F.R. §1.116.

IN THE CLAIMS:

Please amend claims 3, 5 and 10 as follows.

3. (Twice Amended) The apparatus according to claim 1, wherein each of said supply units comprises:

a tank for storing liquid;

a pipe for supplying said liquid from said tank to said mixing unit;